REMARKS

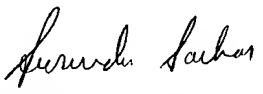
Favorable consideration of this application, as presently amended, is respectfully requested.

The present Preliminary Amendment is submitted to correct for informalities in claims 74 and 107 presented in the Preliminary Amendment filed June 21, 2001, by clarifying certain connections therein. Further, by the present Preliminary Amendment substitute Figures 1-22 are submitted which recite all terms in English, in the event that those figures were not previously submitted.

The present application is believed to be in condition for a full and thorough examination on the merits. An early and favorable consideration of the present application is hereby respectfully requested.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.



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IN THE CLAIMS

Please amend claims 74 and 107 as follows:

--74. (Amended) A position detection apparatus for detecting a position of a mark formed on an object, comprising:

an image pick-up unit which acquires an image pick-up signal by picking up an image of said mark;

the signal processing apparatus according to claim 71, which is electrically connected to the image pick-up unit and performs signal processing for said image pick-up signal as a measurement signal; and

a position calculation unit which is electrically connected to the signal processing apparatus and calculates said position of said mark on the basis of a signal processing result obtained by said signal processing apparatus.

107. (Amended) An exposure apparatus for transferring a predetermined pattern onto a substrate, comprising:

an outer shape specifying unit including the image processing apparatus according to claim 105, which specifies an outer shape of said substrate;

a rotational position control unit which is electrically connected to the outer shape specifying unit and controls a rotational position of said substrate on the basis of said outer shape of said substrate which is specified by said image processing apparatus;

a mark detection unit which detects a mark formed on said substrate whose rotational position is controlled by said rotational position control unit; and

a positioning unit which is electrically connected to the mark detection unit and positions said substrate on the basis of a mark detection result obtained by said mark position detection unit,

wherein said predetermined pattern is transferred onto said substrate while said substrate is positioned by said positioning unit.--